

MURI review

Oct. 2012

G A T O R
Engineering



UNIVERSITY OF
FLORIDA

Topics-role of defects on reliability

I. Effect of Buffer Structures on AlGaN/GaN HEMT Reliability

II. The effects of proton irradiation on the reliability of InAlN/GaN high electron mobility transistors

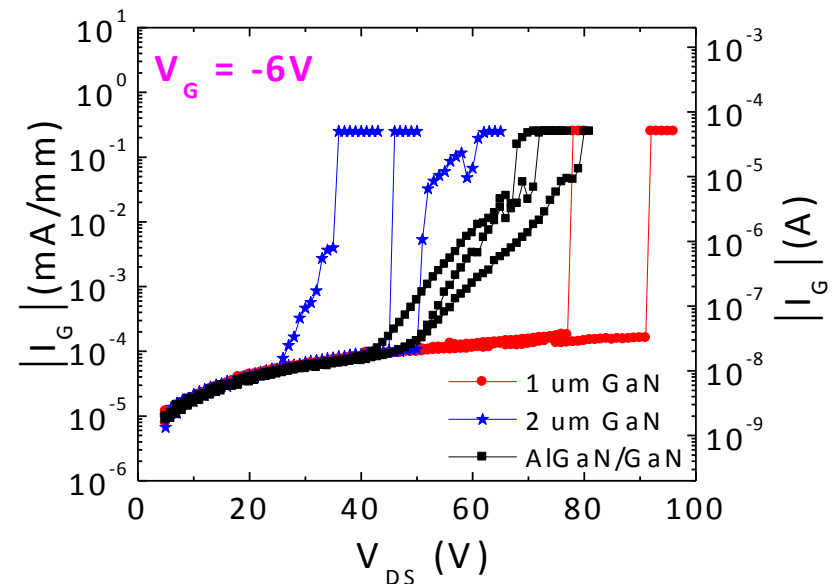
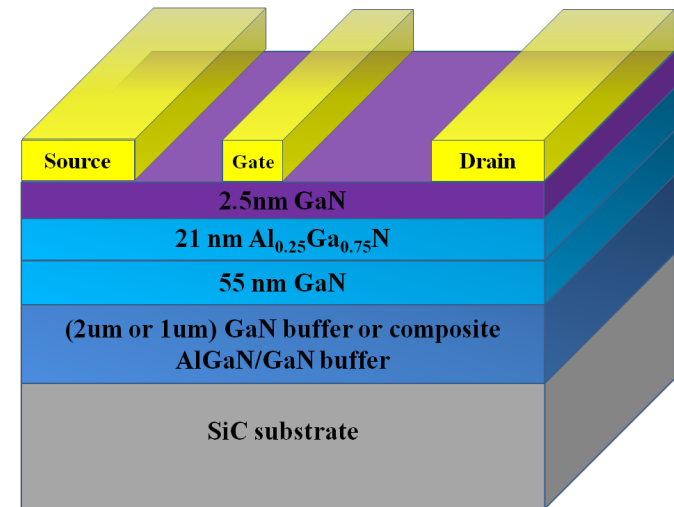
II. Dependence on proton energy of degradation of AlGaN/GaN high electron mobility transistors

Part I

Effect of buffer structures on AlGaIn/GaN HEMT reliability

Results

- **HEMTs with 3 different types of buffer layers, GaN/AlGaN composite layer, or 1 or 2 μm GaN thick layers were compared. Devices with the thick GaN buffer layer showed the lowest critical voltage (V_{cri}) during off-state drain step-stress.**
- **The $V_{off-state}$ for HEMTs with thin GaN and composite buffers were $\sim 100\text{V}$, this degraded to 50-60V for devices with thick GaN buffers.**
- **Peak electric field near the gate edge is reduced for HEMTs with thin buffer layers, this leads to a higher critical voltage for the onset of leakage current and better reliability during bias stressing.**



Part II

The effects of proton irradiation on the reliability of InAlN/GaN high electron mobility transistors

Experiments

Irradiation conditions:

- Proton energies of 5, 10 and 15 MeV at a fixed fluence of $5 \times 10^{15} \text{ cm}^{-2}$;
- Proton doses of 2×10^{11} , 2×10^{13} and $2 \times 10^{15} \text{ cm}^{-2}$ at a fixed energy of 5MeV.

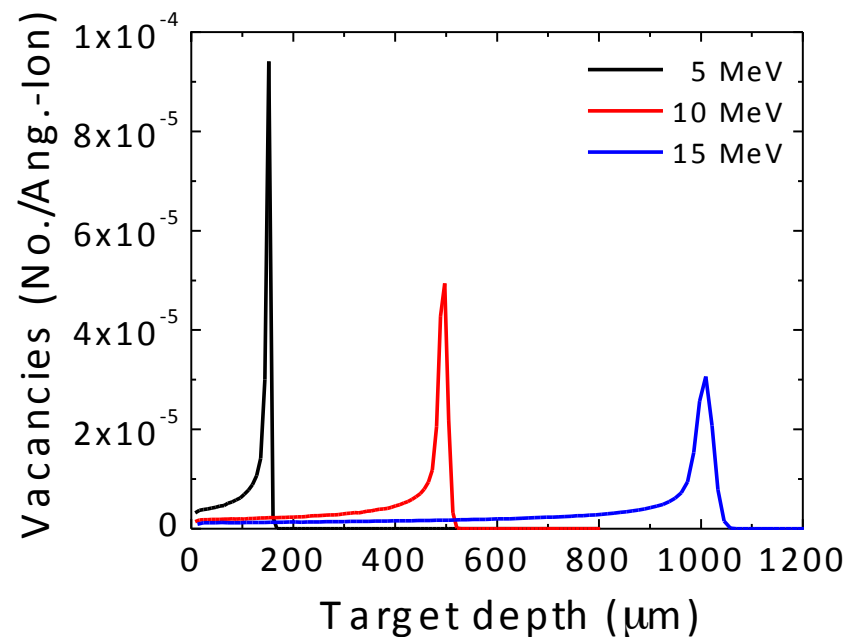
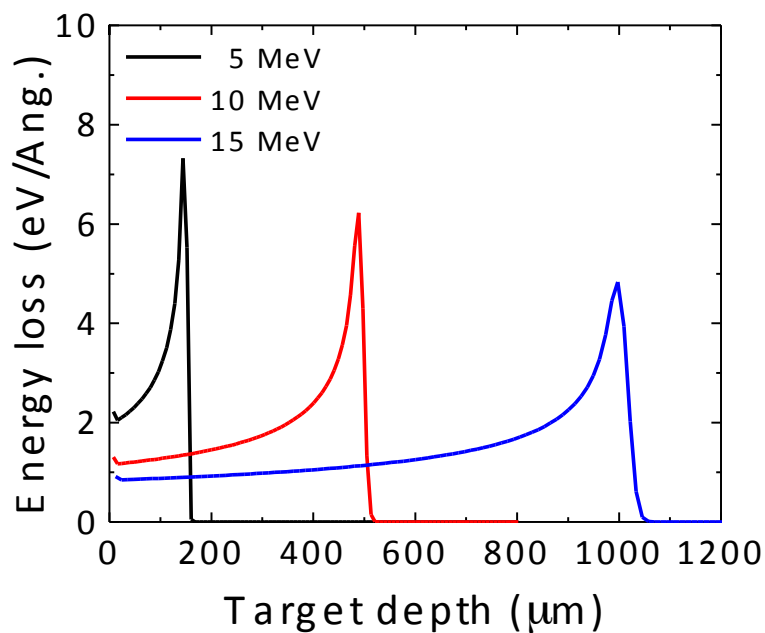
Off-state drain voltage step-stress condition:

Fixed V_G at -6V, stepped drain voltage from +5V to +100V.

Step value = +1V, holding time = 60 sec.

SRIM simulation

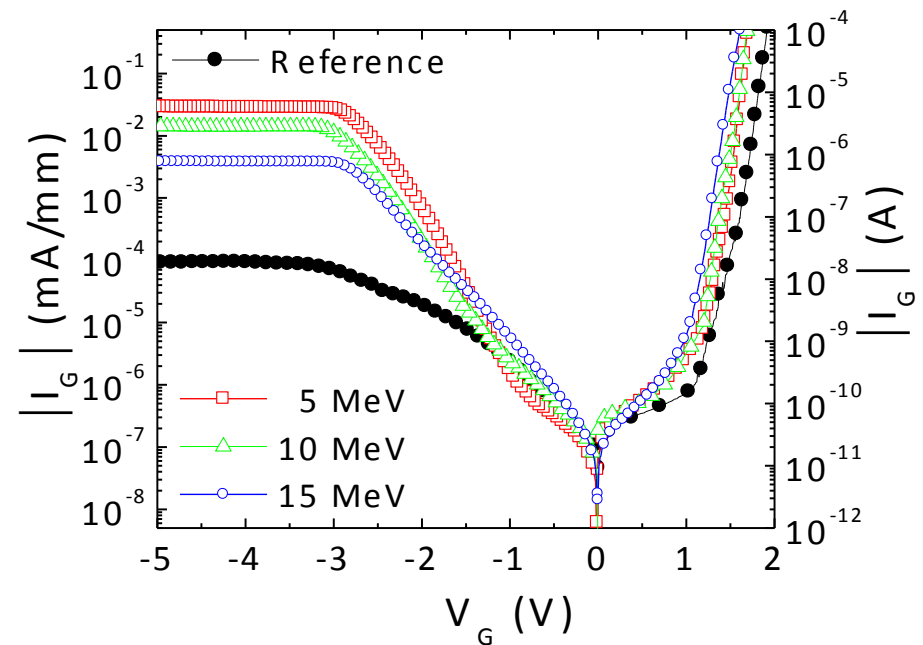
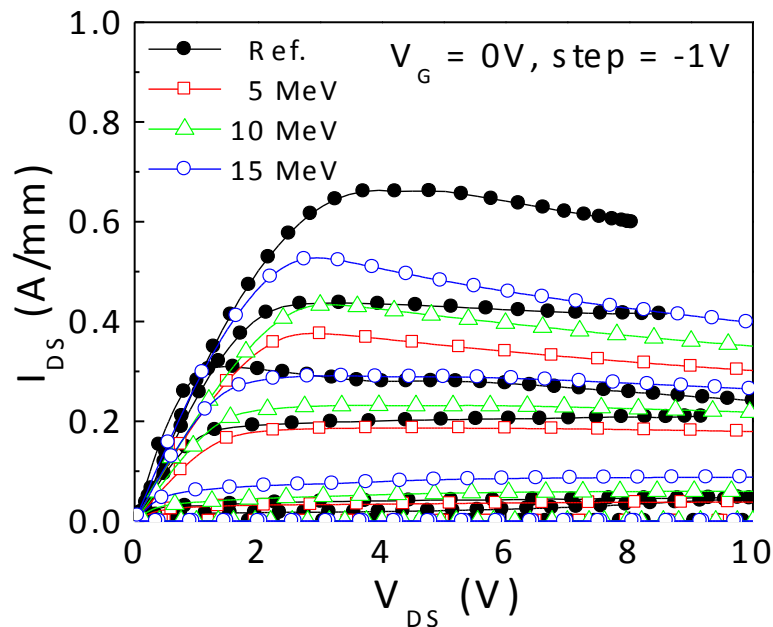
(Stopping and Range of Ions in Matter)



Estimated irradiation-induced vacancy densities around 2-DEG channel range from 5×10^6 to $1.3 \times 10^{11} \text{ cm}^{-2}$ for proton-irradiation energies between 5 and 15 MeV.

DC performance after proton irradiation

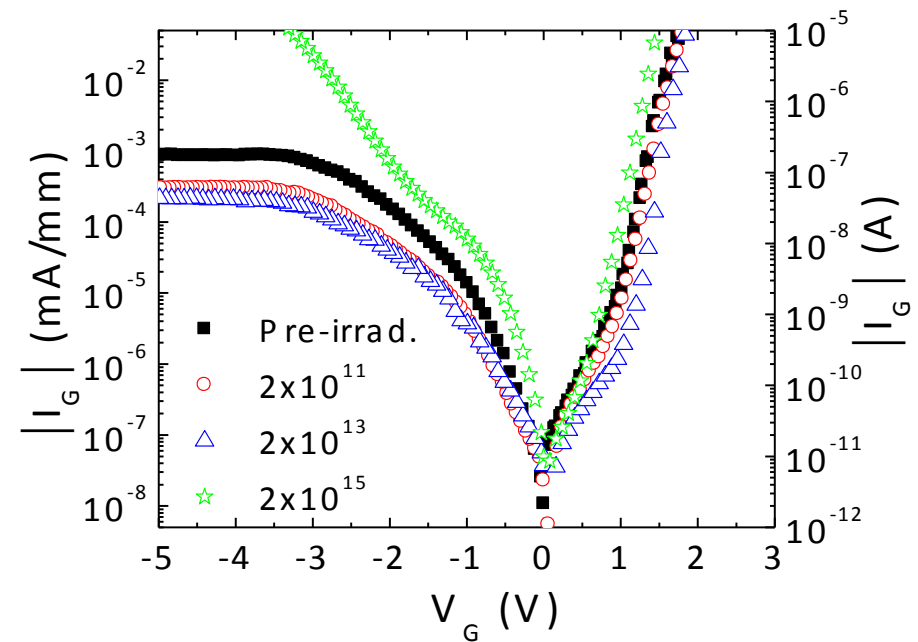
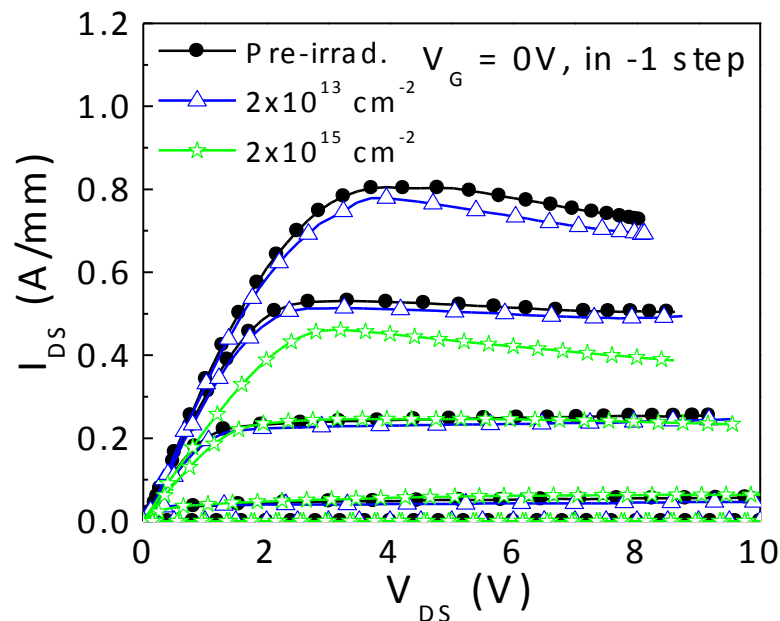
(Fixed dose of $5 \times 10^{15} \text{ cm}^{-2}$)



With lower irradiation energy, more reduction of drain saturation current, higher reverse gate leakage current and lower Schottky barrier height were induced.

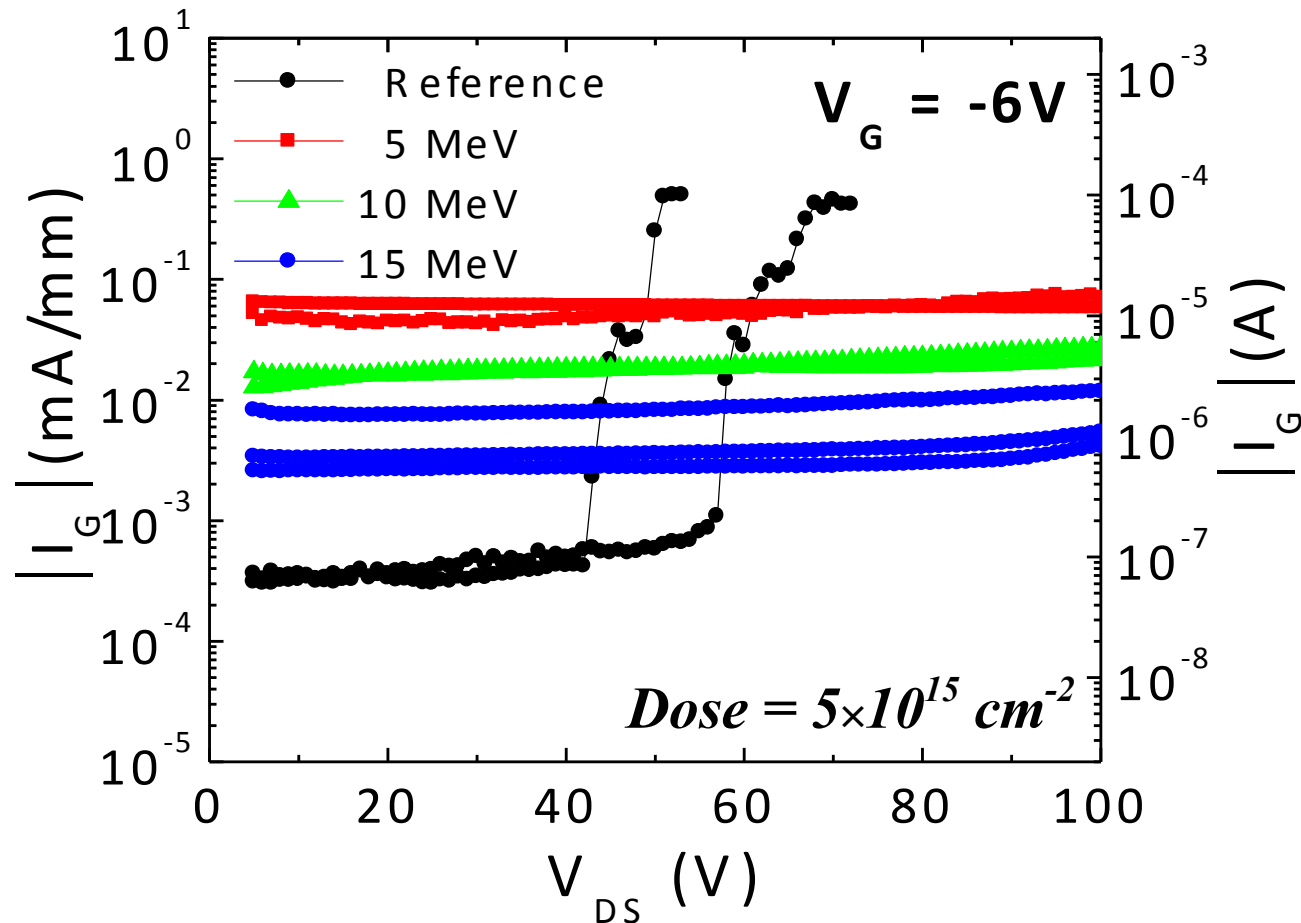
DC performance after proton irradiation

(Fixed energy at 5MeV)



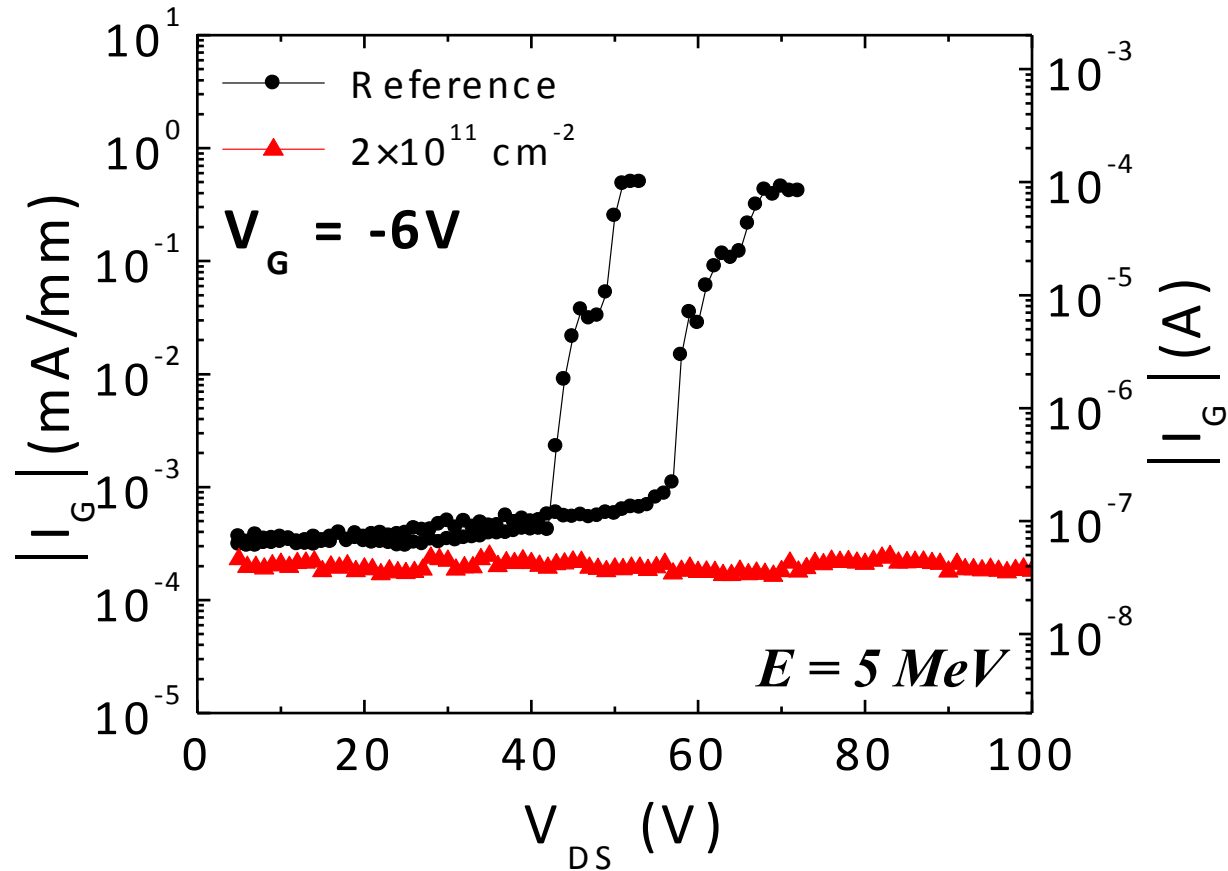
The reduction of drain saturation current increased with irradiation dose.

Electrical stress: (Fixed dose)



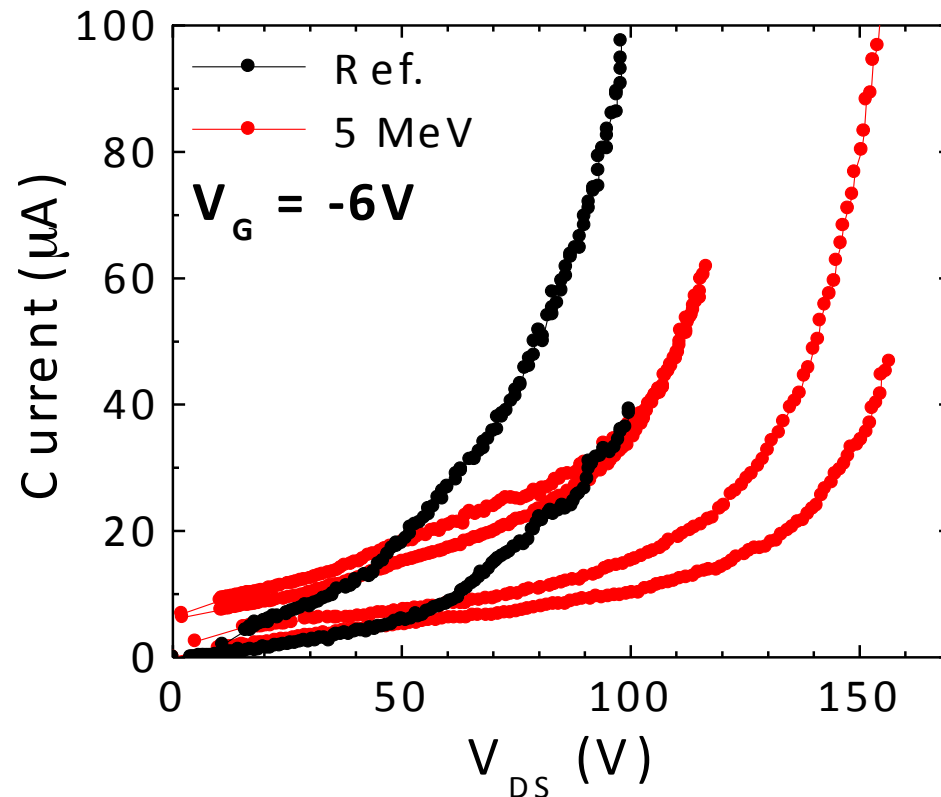
As compared to the un-irradiated HEMTs, apparent reliability of proton-irradiated HEMTs was improved.

Electrical stress: (Fixed energy)



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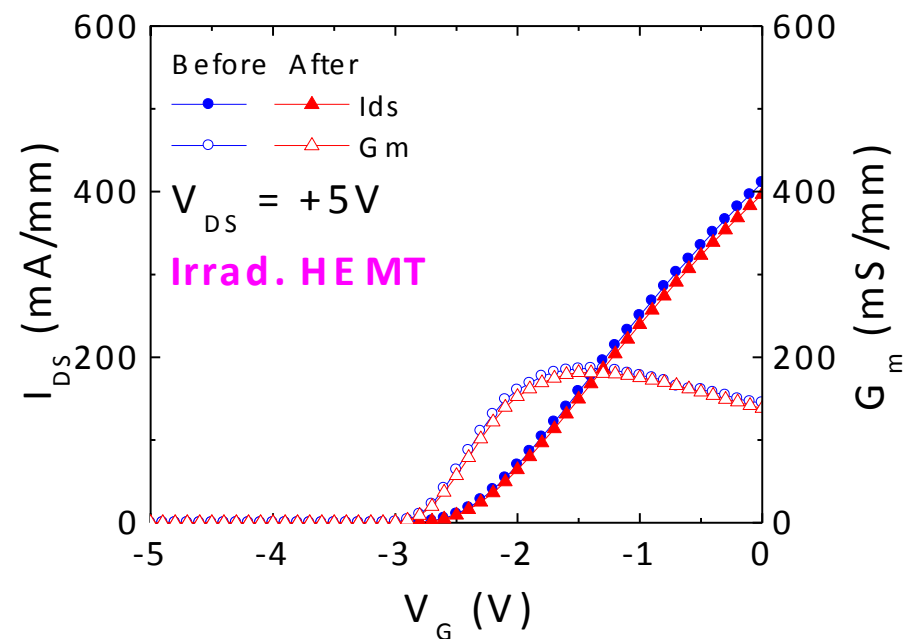
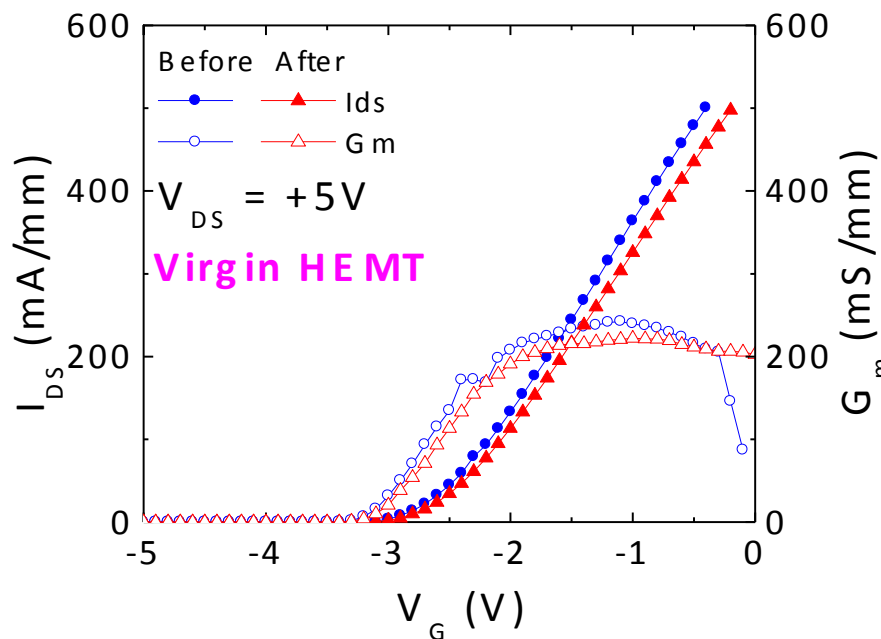
Off-state drain breakdown voltage



**$E = 5\text{ MeV}$
dose = $5 \times 10^{15}\text{ cm}^{-2}$.**

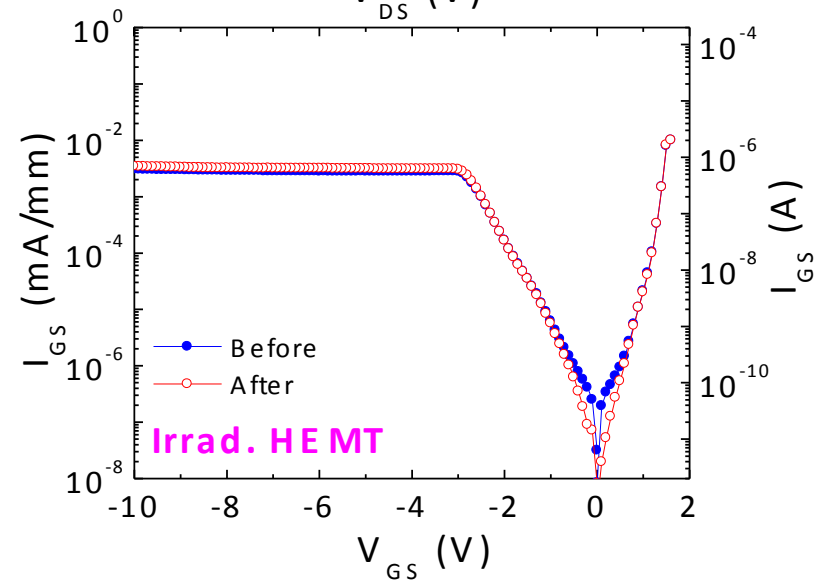
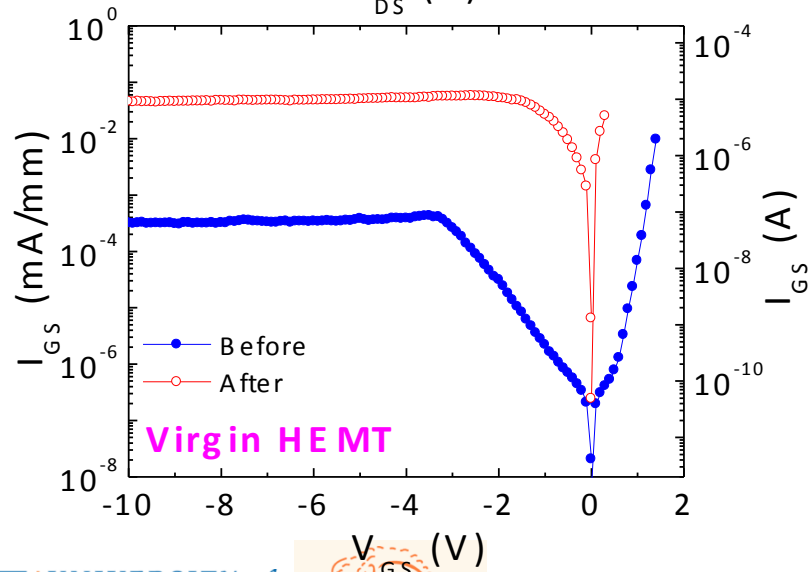
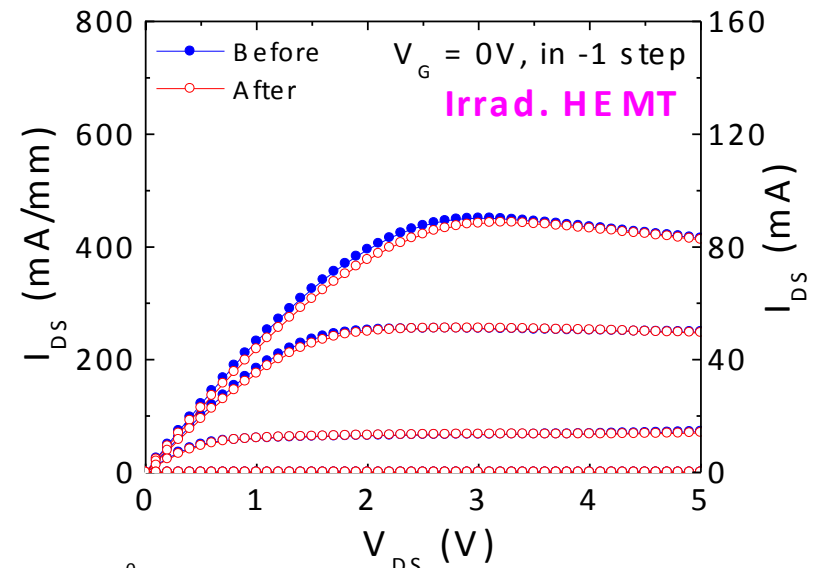
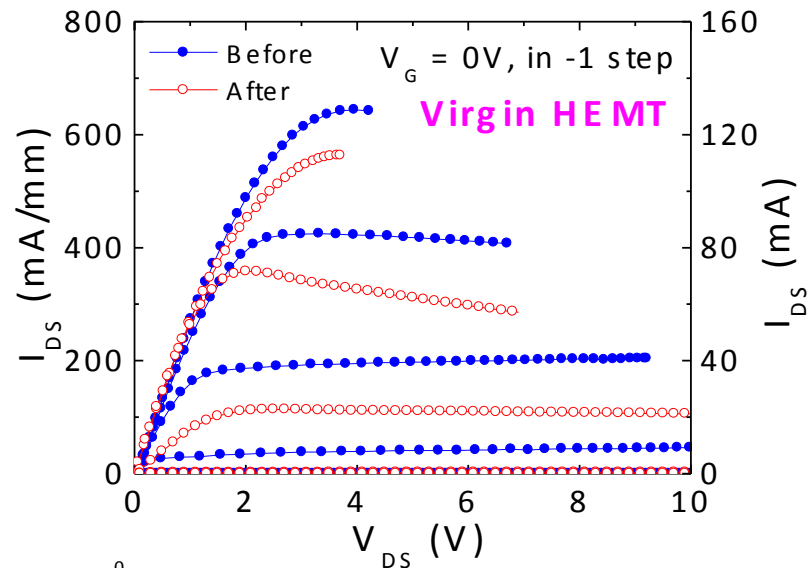
The breakdown voltages increased from ~ 100 V in the reference devices to 160 V in the proton-implantation ones.

Transfer characteristics:

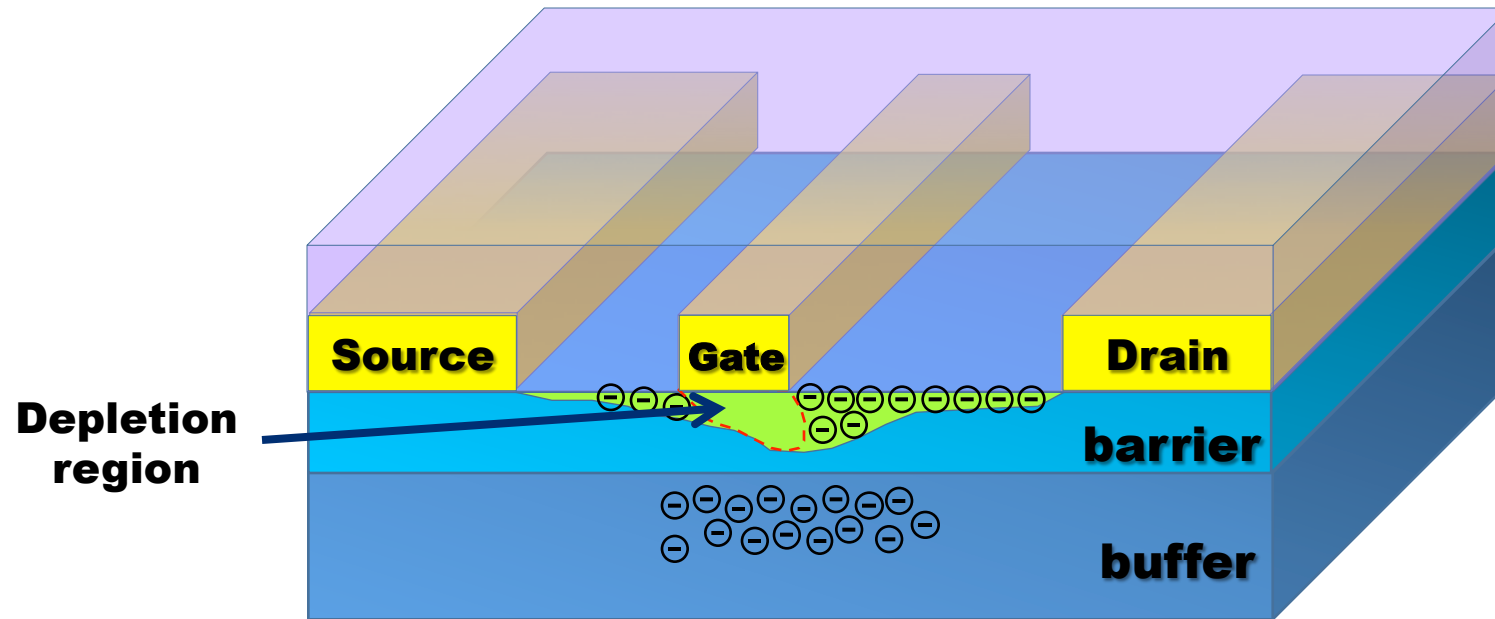


Minimal change was observed for proton-irradiated HEMTs after electrical stress.

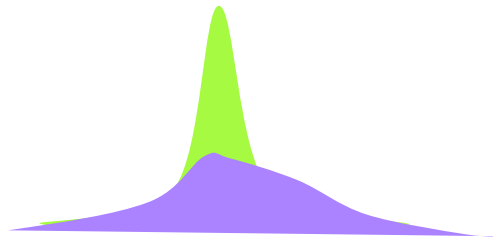
Drain and Gate characteristics:



Proposed mechanism:



Electric field



Part II. Conclusions

- **The critical voltage for off-state drain voltage step-stress was increased from $\sim +50\text{V}$ to **above $+100\text{ V}$** for proton irradiated HEMTs.**
- **There were minimal changes in gate and drain current densities, but much higher critical voltage as well as drain breakdown voltage were observed for the HEMTs irradiated with high energy protons at lower doses. Proton irradiation could be used to improve device reliability.**
- **The large change in critical voltage was tentatively attributed to the virtual gate formation in the damaged buffer layer and lowering of the electrical field around gate.**

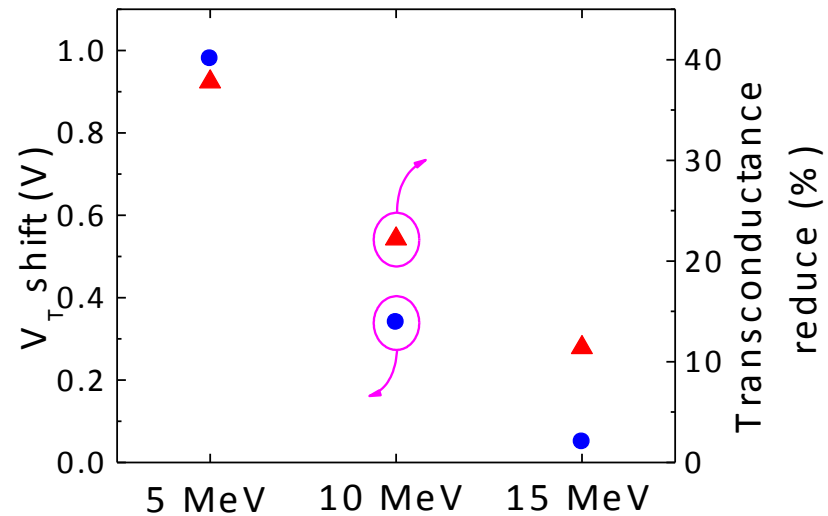
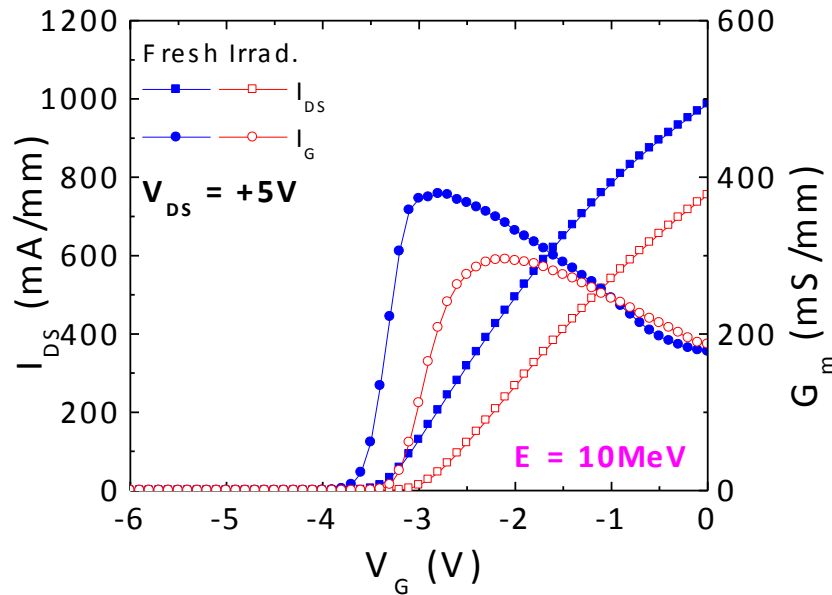
Part III

Dependence on proton energy of degradation of AlGa_N/Ga_N high electron mobility transistors

Experiments

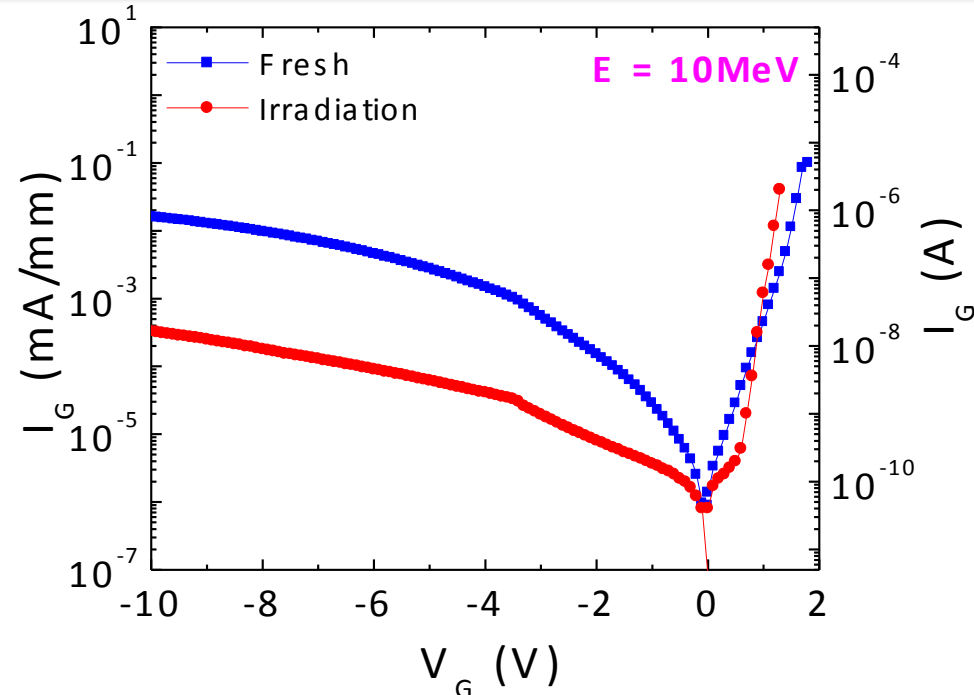
**Proton energies of 5, 10 and 15 MeV
at a fluence of $5 \times 10^{15} \text{ cm}^{-2}$.**

Transfer characteristics:



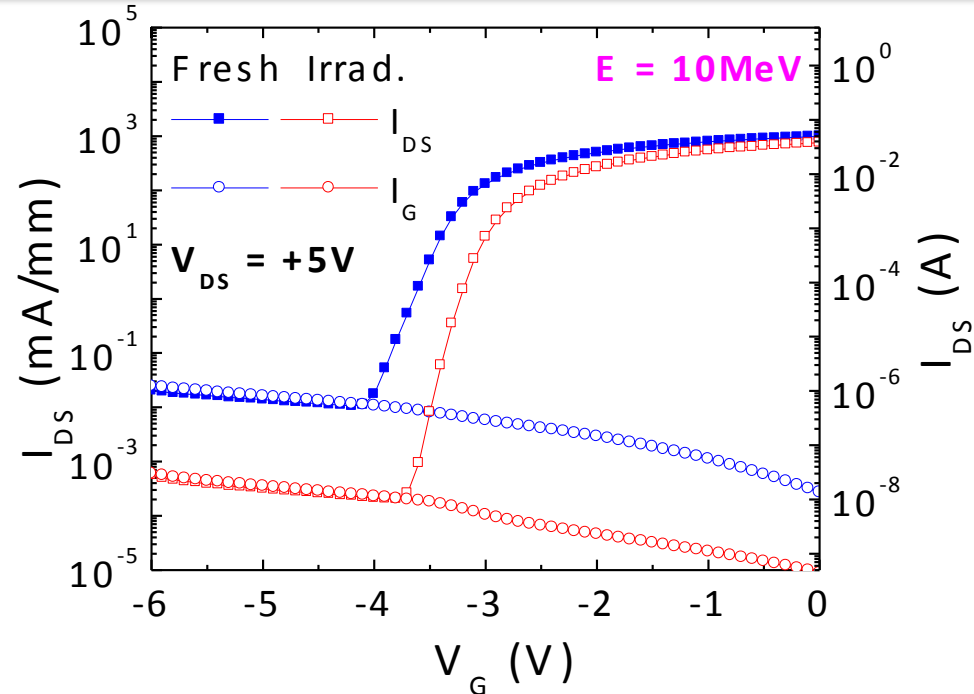
The reductions of maximum transconductance were 11.4, 22.2 and 37.8%, for HEMTs exposed to 15, 10 and 5 MeV protons, respectively.

Gate characteristics:



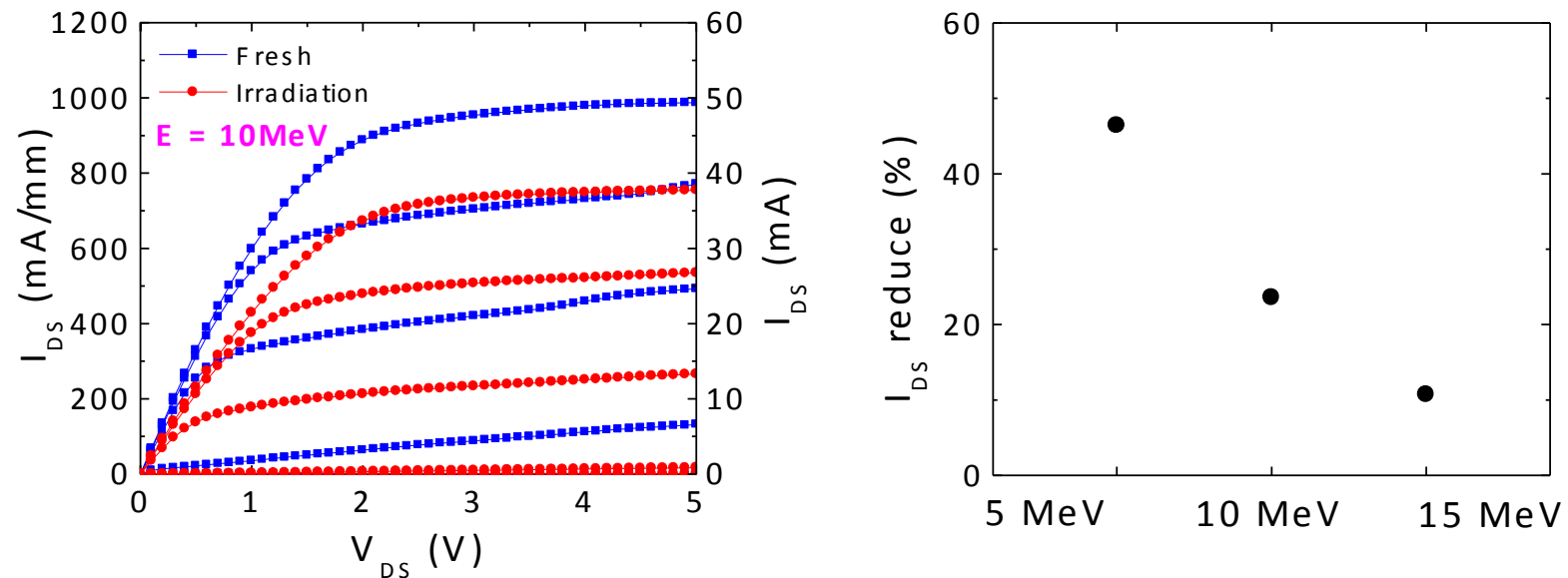
Samples	Condition	I_G at $V_G = -10\text{V}$ (mA/mm)	Schottky barrier height (mV)
5 MeV	<i>Pre-irrad.</i>	1.3×10^{-2}	730
	<i>Post-irrad.</i>	4.5×10^{-4}	790
10 MeV	<i>Pre-irrad.</i>	1.6×10^{-2}	710
	<i>Post-irrad.</i>	3.3×10^{-4}	740
15 MeV	<i>Pre-irrad.</i>	1.7×10^{-2}	660
	<i>Post-irrad.</i>	1.7×10^{-3}	690

Sub-threshold drain and gate leakage:



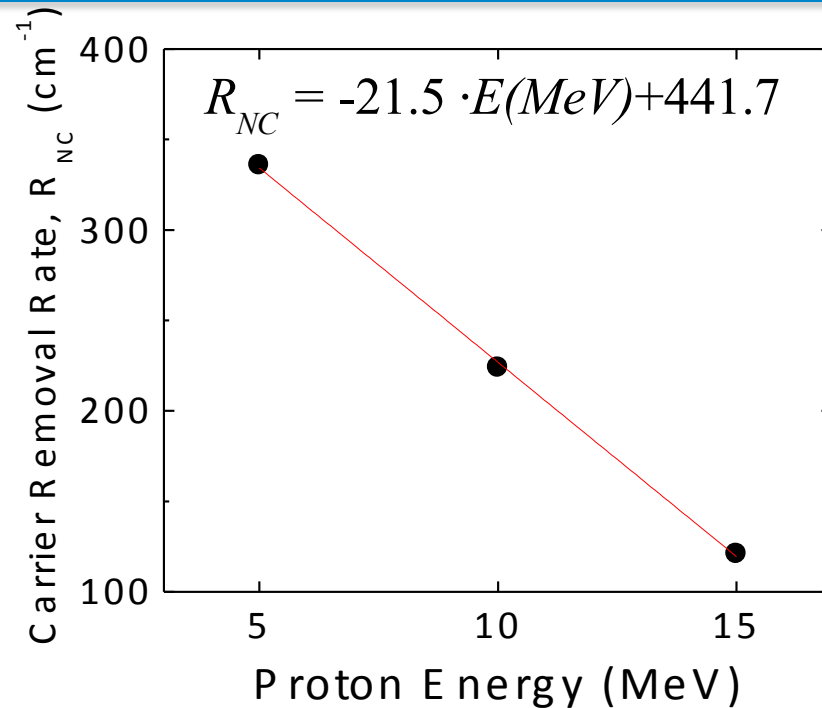
Samples	Condition	ON/OFF ratio	Saturation drain current (mA/mm)	Sub-threshold drain leakage current (mA/mm)	Sub-threshold slope (mV/dec)
5 MeV	<i>Pre-irrad.</i>	6.3×10^4	999	1.6×10^{-2}	179
	<i>Post-irrad.</i>	1.3×10^6	536	4.2×10^{-4}	159
10 MeV	<i>Pre-irrad.</i>	4.9×10^4	986	2.0×10^{-2}	202
	<i>Post-irrad.</i>	1.3×10^6	754	5.6×10^{-4}	124
15 MeV	<i>Pre-irrad.</i>	4.2×10^4	980	2.3×10^{-2}	190
	<i>Post-irrad.</i>	9.9×10^5	885	8.9×10^{-4}	172

Drain characteristics:



The decrease in drain saturation current were 9.6, 23.6 and 46.4% for HEMTs exposed to 15, 10 and 5 MeV protons, respectively.

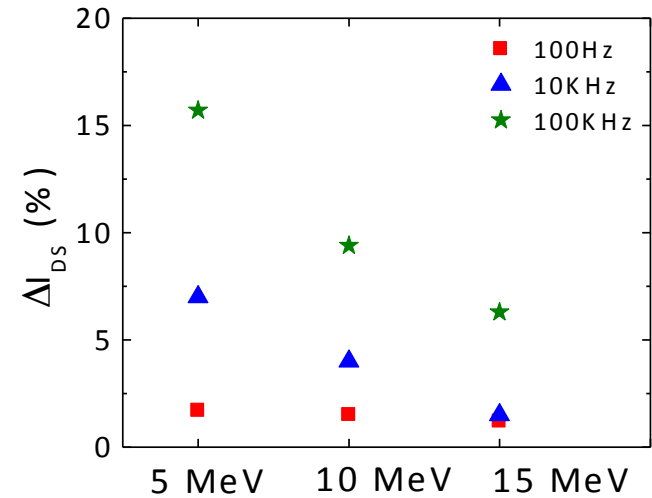
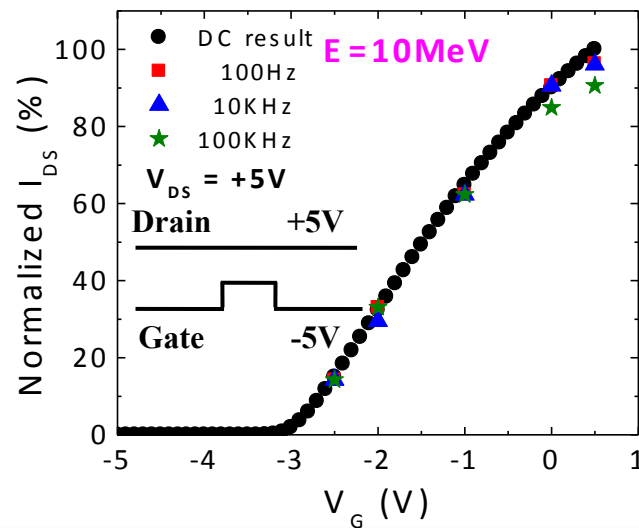
Carrier removal rate:



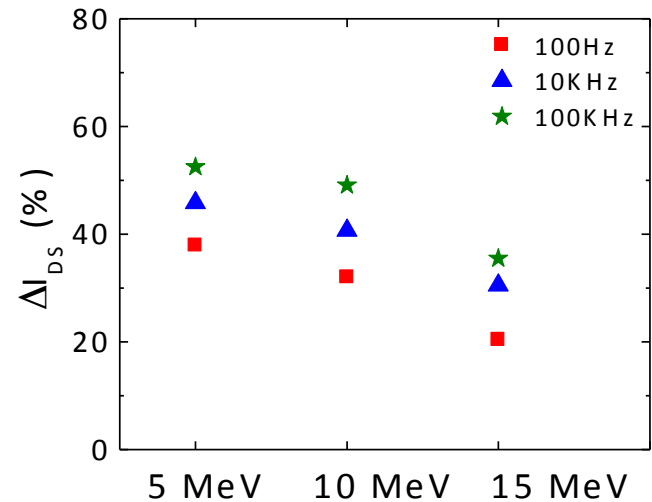
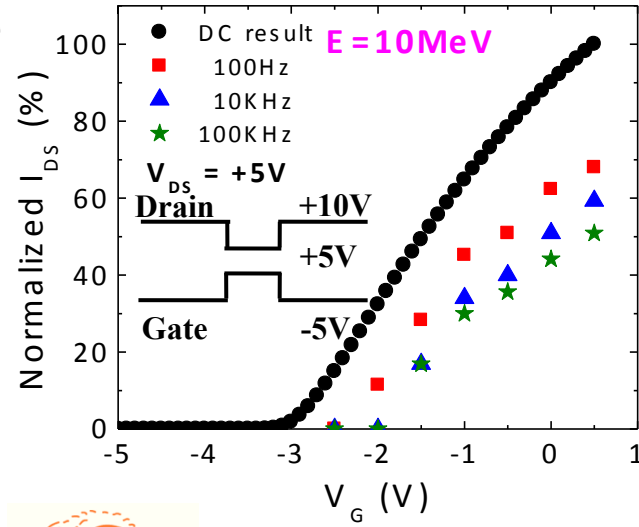
	Pre-irrad.	5 MeV	10 MeV	15 MeV
Normalized mobility	1	0.23	0.38	0.66
Carrier concentration (cm^{-3})	5.8×10^{18}	4.3×10^{18}	4.9×10^{18}	5.1×10^{18}
Sheet carrier concentration (cm^{-2})	7.0×10^{12}	5.2×10^{12}	5.9×10^{12}	6.1×10^{12}
Carrier removal rate (cm^{-1})	—	336	224	121

Pulse measurement:

Gate pulse

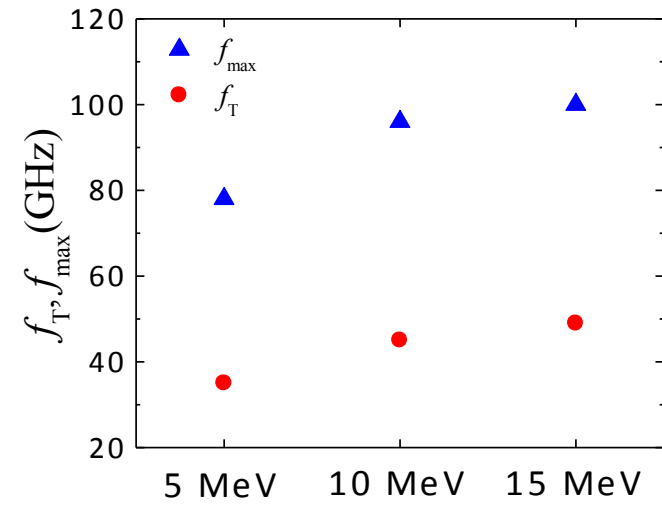
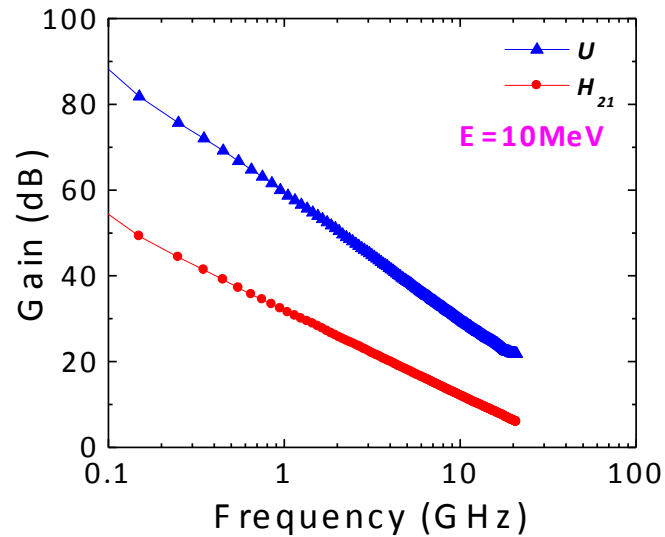


Double pulse

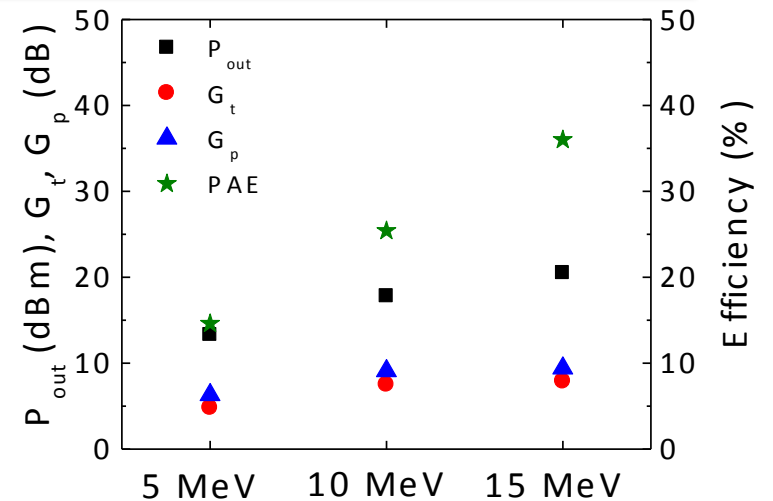
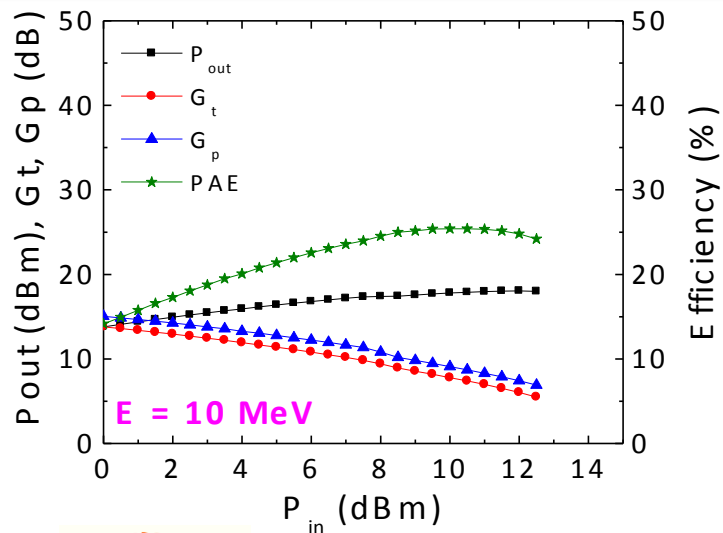


RF measurements:

Small signal



Large signal (10GHz)



Part III. Conclusions

- **Reductions of transconductance peak were 11.4%, 22.2 and 37.4 % and of drain saturation current at $V_G = 0V$ were 9.6%, 23.6% and 46.4% for HEMTs irradiated at 15, 10 and 5 MeV, respectively.**
- **After irradiation, sub-threshold drain leakage current and reverse gate I-V decreased more than one order of magnitude for all cases.**
- **The irradiation-induced displacement damage mechanism, which reduced carrier mobility and charge density, was responsible for more degradation at lower irradiation energy, since more defect centers were introduced close to the 2DEG channel.**